

# Kenneth Gonsalves

## List of Publications by Year in descending order

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53  
papers

706  
citations

471509

17  
h-index

580821

25  
g-index

57  
all docs

57  
docs citations

57  
times ranked

558  
citing authors

#	ARTICLE	IF	CITATIONS
1	Micropatterns of a Cell-Adhesive Peptide on an Amphiphilic Comb Polymer Film. <i>Langmuir</i> , 2002, 18, 2975-2979.	3.5	53
2	Novel polymeric anionic photoacid generators (PAGs) and corresponding polymers for 193 nm lithography. <i>Journal of Materials Chemistry</i> , 2006, 16, 3701.	6.7	44
3	Radiation-Sensitive Novel Polymeric Resist Materials: Iterative Synthesis and Their EUV Fragmentation Studies. <i>ACS Applied Materials &amp; Interfaces</i> , 2014, 6, 4223-4232.	8.0	44
4	Novel anionic photoacid generators (PAGs) and corresponding PAG bound polymers for sub-50 nm EUV lithography. <i>Journal of Materials Chemistry</i> , 2007, 17, 1699.	6.7	40
5	New Polyoxometalates Containing Hybrid Polymers and Their Potential for Nano-Patterning. <i>Chemistry - A European Journal</i> , 2015, 21, 2250-2258.	3.3	32
6	Recent advances in non-chemically amplified photoresists for next generation IC technology. <i>RSC Advances</i> , 2016, 6, 74462-74481.	3.6	32
7	Development of Nickel-Based Negative Tone Metal Oxide Cluster Resists for Sub-10 nm Electron Beam and Helium Ion Beam Lithography. <i>ACS Applied Materials &amp; Interfaces</i> , 2020, 12, 19616-19624.	8.0	30
8	Novel chemically amplified resists incorporating anionic photoacid generator functional groups for sub-50-nm half-pitch lithography. <i>Journal of Materials Chemistry</i> , 2009, 19, 2797.	6.7	29
9	Design, development, EUVL applications and nano mechanical properties of a new HfO <sub>2</sub> based hybrid non-chemically amplified resist. <i>RSC Advances</i> , 2016, 6, 67143-67149.	3.6	28
10	Micro/nanomachining of Polymer Surface for Promoting Osteoblast Cell Adhesion. <i>Biomedical Microdevices</i> , 2003, 5, 101-108.	2.8	25
11	EUV photofragmentation study of hybrid nonchemically amplified resists containing antimony as an absorption enhancer. <i>RSC Advances</i> , 2018, 8, 10930-10938.	3.6	24
12	Performance evaluation of nonchemically amplified negative tone photoresists for e-beam and EUV lithography. <i>Journal of Micro/ Nanolithography, MEMS, and MOEMS</i> , 2014, 13, 043002.	0.9	22
13	Towards novel non-chemically amplified (n-CARS) negative resists for electron beam lithography applications. <i>Journal of Materials Chemistry C</i> , 2014, 2, 2118.	5.5	21
14	Polyarylenesulfonium Salt as a Novel and Versatile Nonchemically Amplified Negative Tone Photoresist for High-Resolution Extreme Ultraviolet Lithography Applications. <i>ACS Applied Materials &amp; Interfaces</i> , 2017, 9, 17-21.	8.0	21
15	Organotin in Nonchemically Amplified Polymeric Hybrid Resist Imparts Better Resolution with Sensitivity for Next-Generation Lithography. <i>ACS Applied Polymer Materials</i> , 2020, 2, 1790-1799.	4.4	21
16	Novel Anionic Photoacid Generators (PAGs) and Corresponding PAG Bound Polymers. <i>Macromolecular Rapid Communications</i> , 2006, 27, 1590-1595.	3.9	20
17	Selective Fragmentation of Radiation-Sensitive Novel Polymeric Resist Materials by Inner-Shell Irradiation. <i>ACS Applied Materials &amp; Interfaces</i> , 2015, 7, 16348-16356.	8.0	18
18	Incorporation of ionic photoacid generator (PAG) and base quencher into the resist polymer main chain for sub-50 nm resolution patterning. <i>Journal of Materials Chemistry</i> , 2008, 18, 2704.	6.7	16

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19	Resists for Helium Ion Beam Lithography: Recent Advances. ACS Applied Electronic Materials, 2020, 2, 3805-3817.	4.3	16
20	Organoiodine Functionality Bearing Resists for Electron-Beam and Helium Ion Beam Lithography: Complex and Sub-16 nm Patterning. ACS Applied Electronic Materials, 2021, 3, 1996-2004.	4.3	16
21	Organic-inorganic hybrid photoresists containing hexafluoroantimonate: design, synthesis and high resolution EUV lithography studies. Materials Chemistry Frontiers, 2017, 1, 2613-2619.	5.9	13
22	Heavy metal incorporated helium ion active hybrid non-chemically amplified resists: Nano-patterning with low line edge roughness. AIP Advances, 2017, 7, 085314.	1.3	12
23	EUV photofragmentation and oxidation of a polyarylene Sulfonium resist: XPS and NEXAFS study. Journal of Photochemistry and Photobiology A: Chemistry, 2018, 364, 373-381.	3.9	12
24	A photoacid generator integrated terpolymer for electron beam lithography applications: sensitive resist with pattern transfer potential. Materials Chemistry Frontiers, 2017, 1, 1895-1899.	5.9	11
25	Mechanistic insights of Sn-based non-chemically-amplified resists under EUV irradiation. Applied Surface Science, 2020, 533, 146553.	6.1	10
26	Cell Behavior Toward Nanostructured Surfaces. , 0, , 261-295.		9
27	Patterning highly ordered arrays of complex nanofeatures through EUV directed polarity switching of non chemically amplified photoresist. Scientific Reports, 2016, 6, 22664.	3.3	9
28	The effect of direct PAG incorporation into the polymer main chain on reactive ion etch resistance of 193nm and EUV chemically amplified resists. Microelectronic Engineering, 2008, 85, 963-965.	2.4	8
29	Design and development of low activation energy based nonchemically amplified resists (n-CARs) for next generation EUV lithography. Microelectronic Engineering, 2016, 164, 115-122.	2.4	7
30	Functionalized Ag Nanoparticles Embedded in Polymer Resists for High-Resolution Lithography. ACS Applied Nano Materials, 2020, 3, 8651-8661.	5.0	7
31	Nanostructures for Tissue Engineering/Regenerative Medicine. , 0, , 375-407.		5
32	Polymeric Nanoparticles and Nanopore Membranes for Controlled Drug and Gene Delivery. , 0, , 115-137.		5
33	Nanotechnology and Drug Delivery. , 0, , 93-113.		4
34	Multiscale Coculture Models for Orthopedic Interface Tissue Engineering. , 0, , 357-373.		4
35	ECM Interactions with Cells from the Macro- to Nanoscale. , 0, , 223-260.		4
36	Enhanced mechanical properties of the high-resolution EUVL patterns of hybrid photoresists containing hexafluoroantimonate. Microelectronic Engineering, 2018, 194, 100-108.	2.4	4

#	ARTICLE	IF	CITATIONS
37	Fullerene Grafted Photoacid Generator (PAG) Bound Polymer Resists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2008, 21, 747-751.	0.3	3
38	A Versatile Approach for Biomaterial Patterning: Masked Ion Beam Lithography. Materials Research Society Symposia Proceedings, 2001, 705, 461.	0.1	2
39	Cellular Behavior on Basement Membrane Inspired Topographically Patterned Synthetic Matrices. , 0, , 297-319.		2
40	Nanostructures for Cancer Diagnostics and Therapy. , 0, , 409-437.		2
41	Micro/Nanomachining and Fabrication of Materials for Biomedical Applications. , 0, , 25-47.		2
42	Ferrocene Bearing Non-ionic Poly-aryl Tosylates: Synthesis, Characterization and Electron Beam Lithography Applications. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 669-678.	0.3	2
43	Polarization Dependence in the Carbon K-Edge Photofragmentation of MAPDST Photoresist: An Experimental and Theoretical Study. Journal of Physical Chemistry C, 2018, 122, 28619-28628.	3.1	2
44	Development of Nanostructures for Drug Delivery Applications. , 0, , 139-206.		1
45	Nanoscale Iron Compounds Related to Neurodegenerative Disorders. , 0, , 461-490.		1
46	Bioconjugated Nanoparticles for Ultrasensitive Detection of Molecular Biomarkers and Infectious Agents. , 0, , 207-222.		1
47	New Photoresists with Photoacid Generator in the Backbone. Materials Research Society Symposia Proceedings, 2001, 705, 231.	0.1	0
48	Nanofabrication Techniques. , 0, , 1-24.		0
49	Focal Adhesions: Self-Assembling Nanoscale Mechanochemical Machines that Control Cell Function. , 0, , 321-335.		0
50	Controlling Cell Behavior via DNA and RNA Transfections. , 0, , 337-356.		0
51	Application of Nanotechnology into Life Science: Benefit or Risk. , 0, , 491-501.		0
52	Novel Nanostructures as Molecular Nanomotors. , 0, , 49-60.		0
53	Bioconjugation of Soft Nanomaterials. , 0, , 61-91.		0